

Chloride-Induced Aufbau of Cyclohexasilanes from Si_2Cl_6

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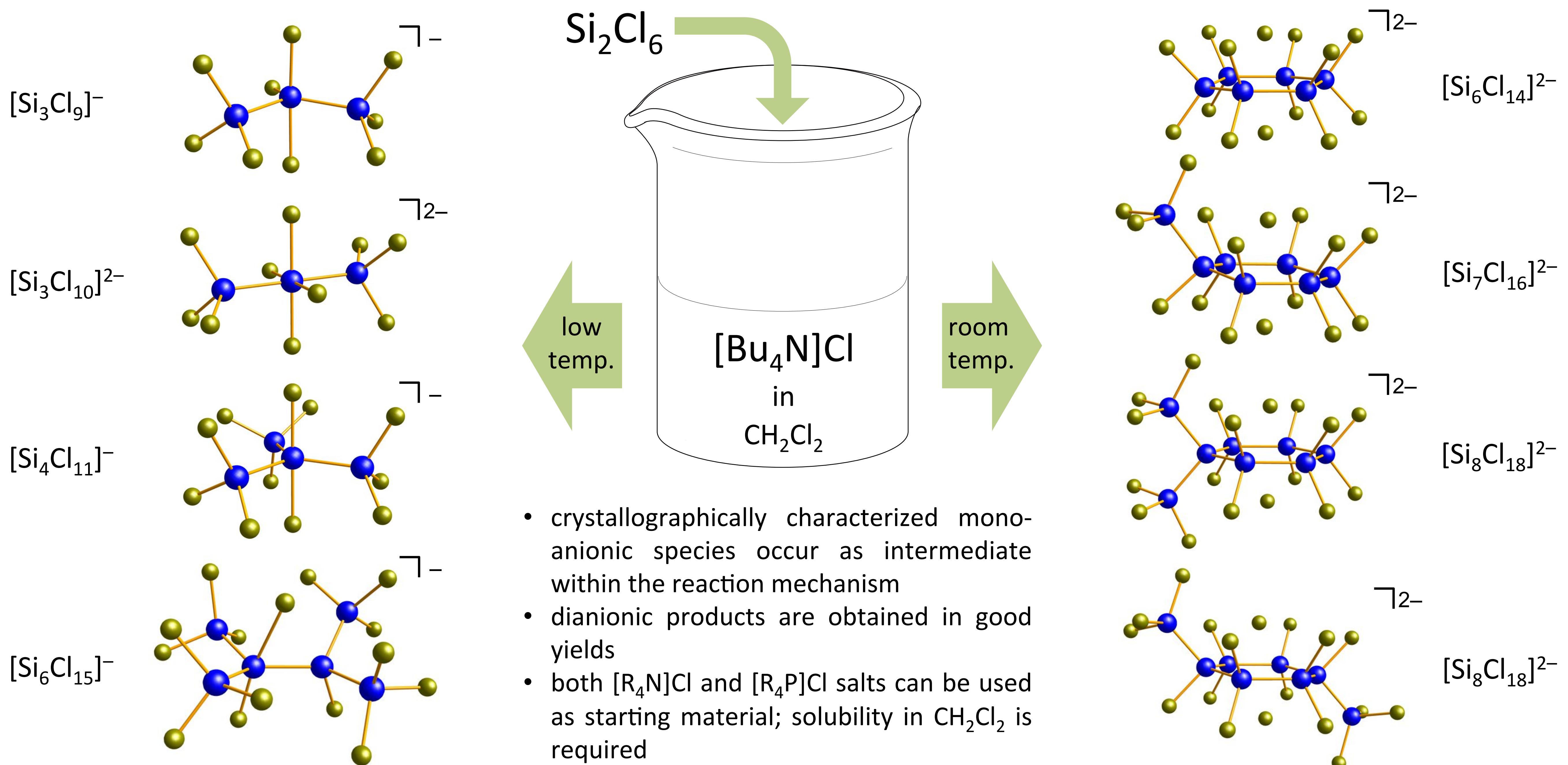
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Introduction

Thin films of nano-crystalline, micro-crystalline and amorphous silicon (Si) are and will be an important element of present and future semiconductors. Until today such Si-films are fabricated through gas-phase deposition of smaller silanes, originating from the reduction of the corresponding chlorosilanes. Solution-based methods, such as spin-, spray- or printing processes, provide a promising approach to improve the manufacturing of Si-films.

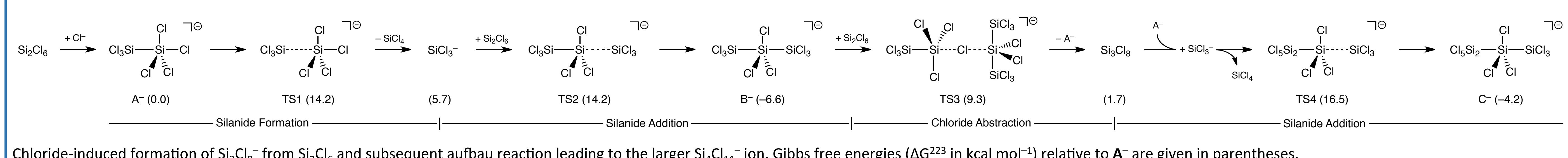
Therefore, higher oligosilanes with boiling points above their deposition temperatures are in demand. Known synthetic routes are too laborious and expensive to be used in large-scale production. We therefore suggest a synthesis strategy offering convenient access to oligochlorosilane precursors: the chloride-induced formation of chloride-complexed cyclic dianions upon addition of Si_2Cl_6 to a solution of $[\text{Bu}_4\text{N}]\text{Cl}$ in CH_2Cl_2 .^[1]

Chloride-Induced Aufbau of Higher Perchlorated Silanes

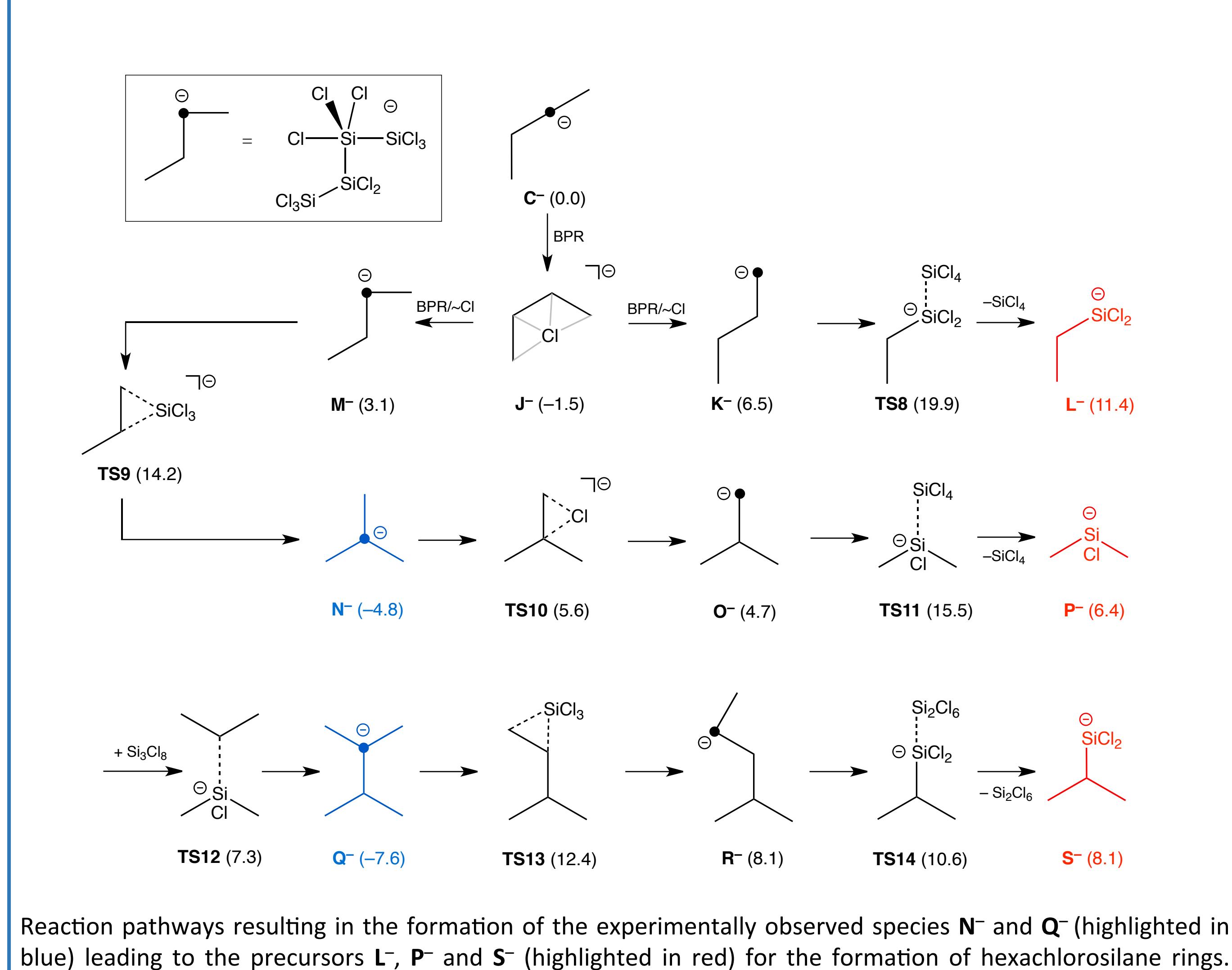


Mechanistic Scenario According to Experimental and Quantum-Chemical Studies

Elementary Steps of the Aufbau Reaction



Aufbau Reaction of Higher Silanides



Formation of (Silyl-Substituted) Hexasilanes

